

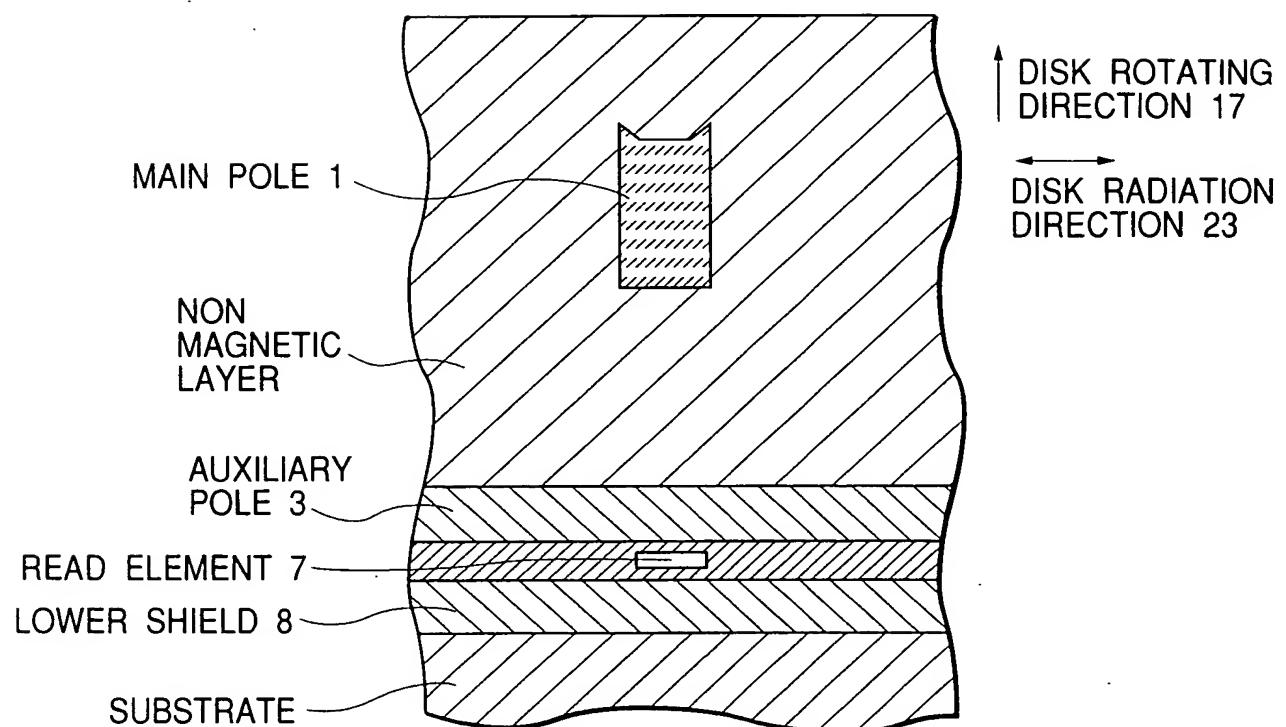
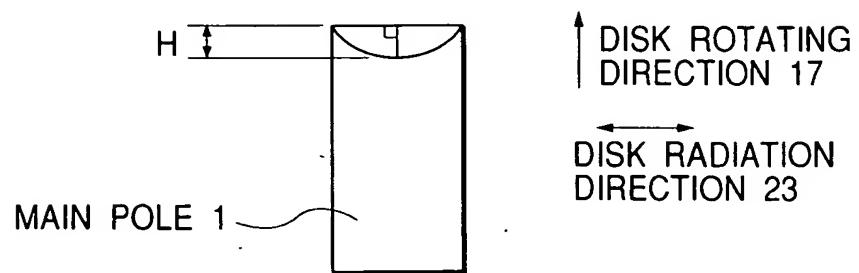
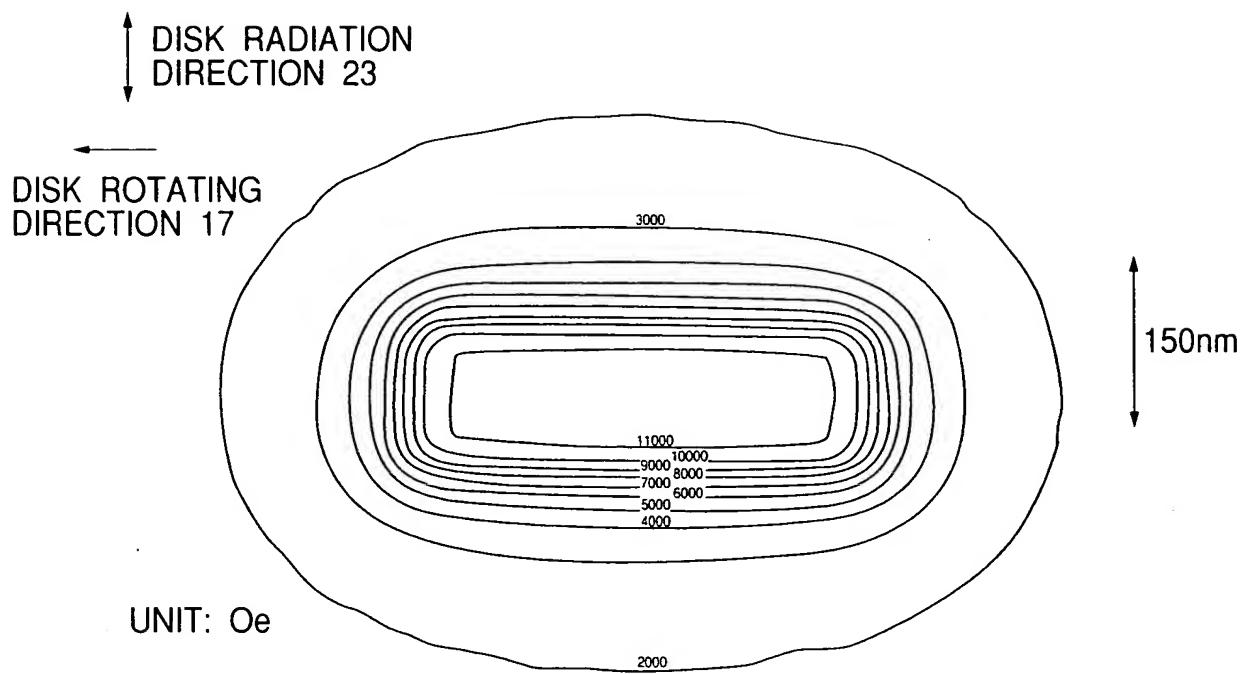
FIG. 1(A)**FIG. 1(B)**

FIG. 2(A)



CONTOURS OF PERPENDICULAR COMPONENT OF WRITE FIELD GENERATED FROM A SINGLE POLE TYPE HEAD

FIG. 2(B)

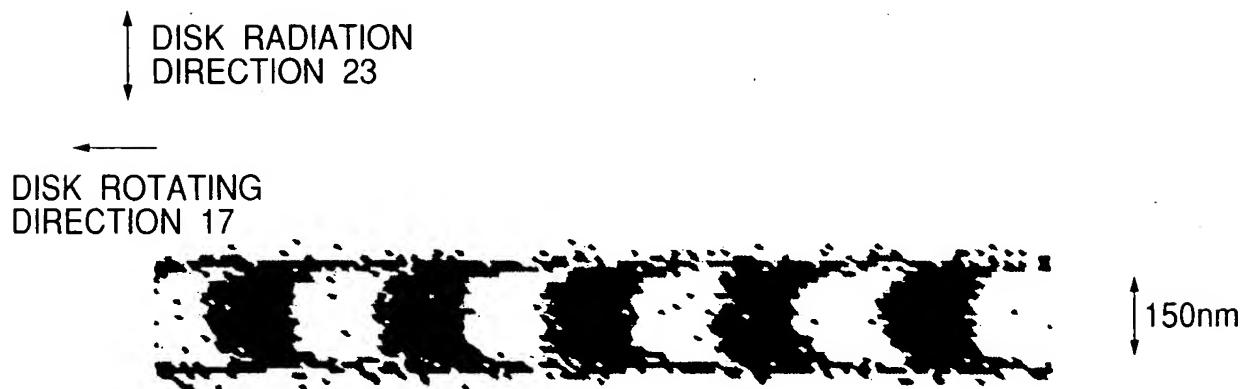


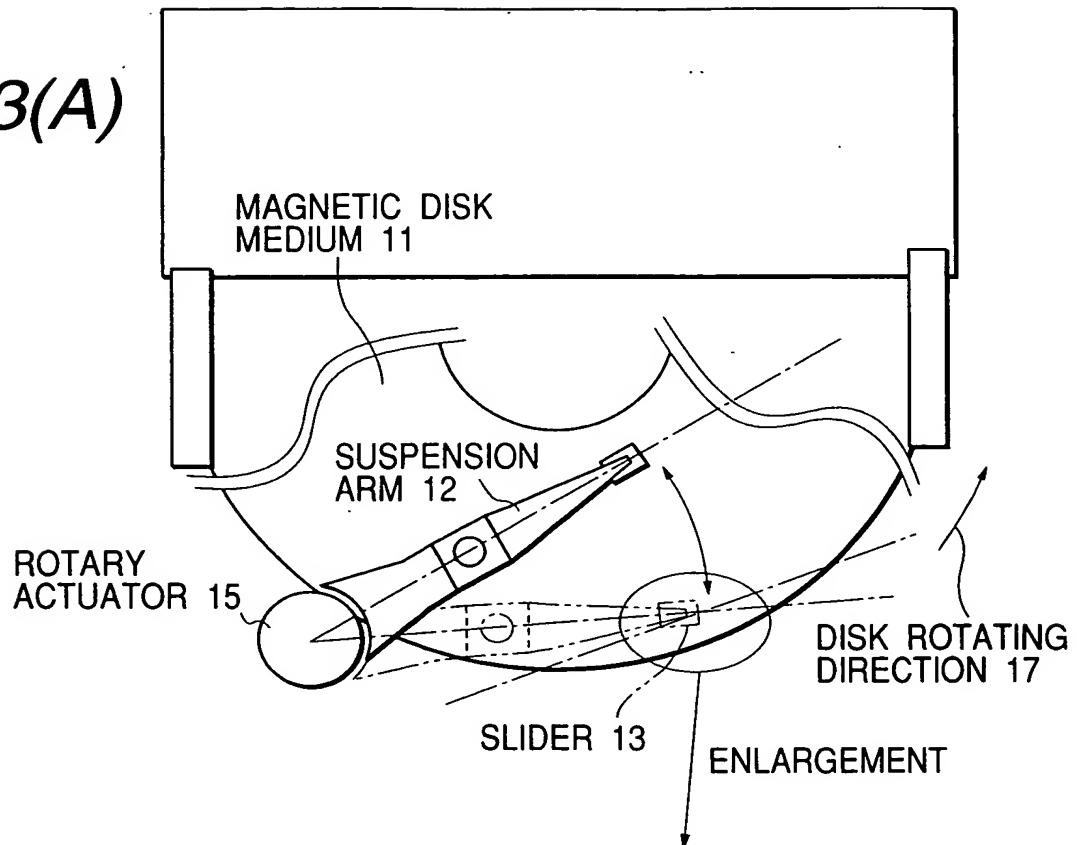
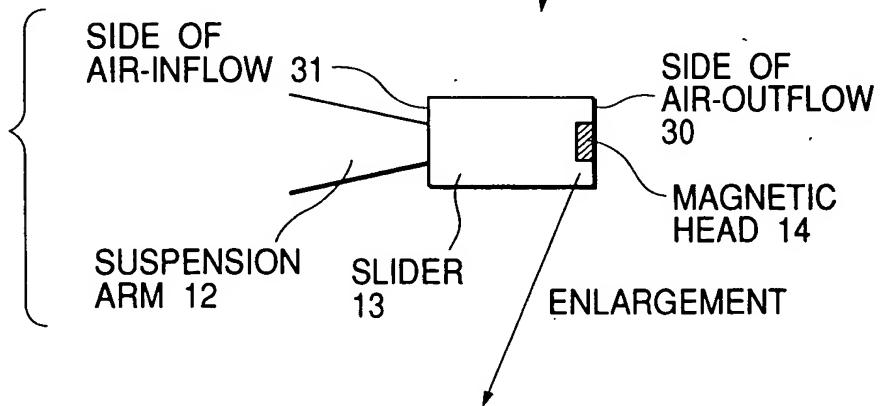
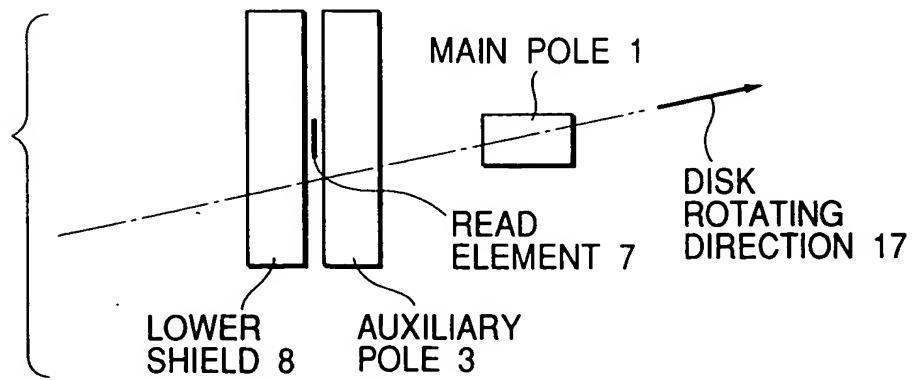
FIG. 3(A)**FIG. 3(B)****FIG. 3(C)**

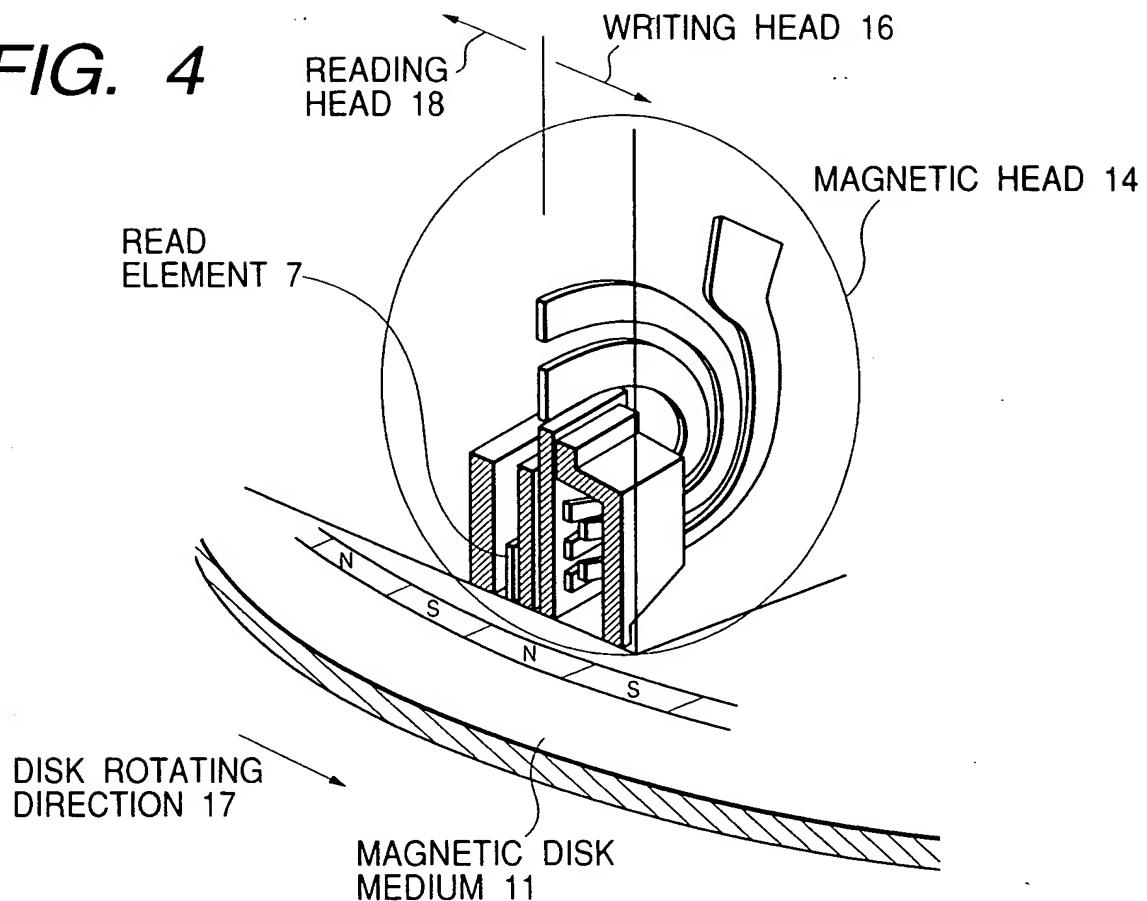
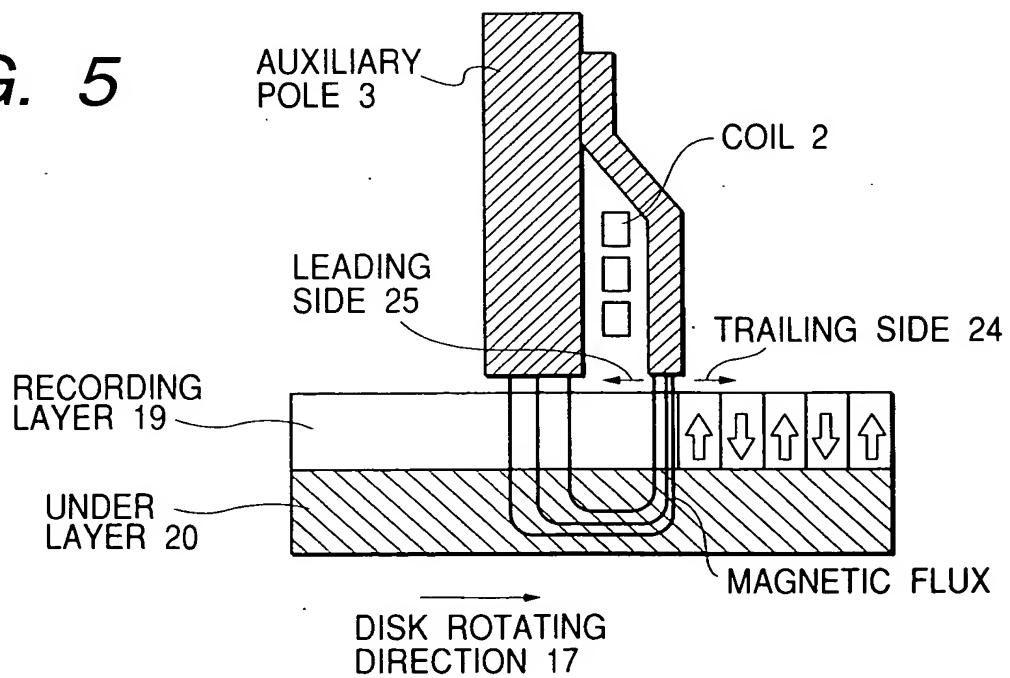
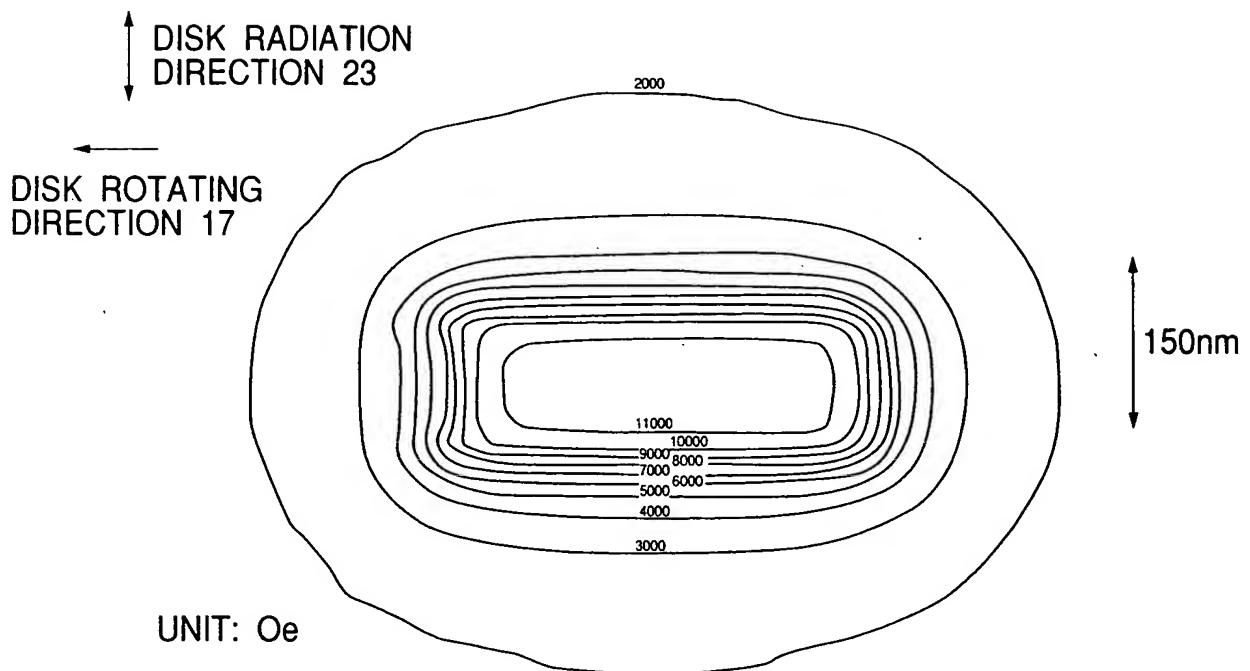
FIG. 4**FIG. 5**

FIG. 6(A)



CONTOURS OF PERPENDICULAR COMPONENT OF WRITE FIELD GENERATED FROM A SINGLE POLE TYPE HEAD

FIG. 6(B)



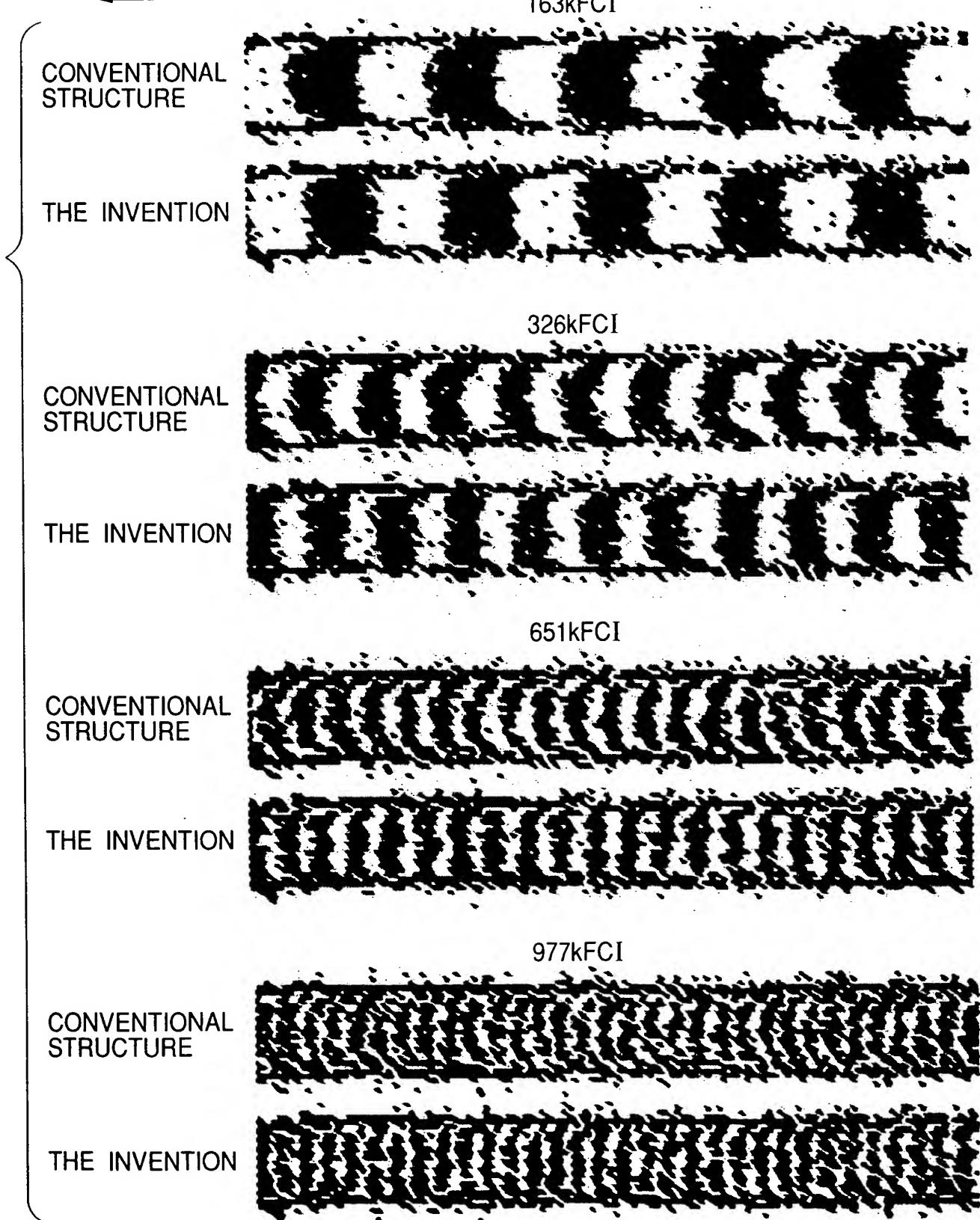
FIG. 7DISK ROTATING
DIRECTION 17

FIG. 8(A)

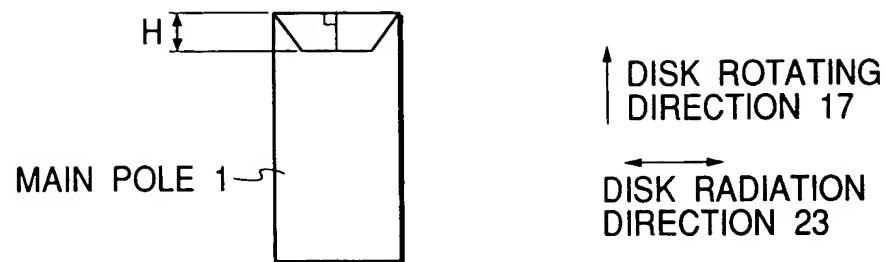


FIG. 8(B)

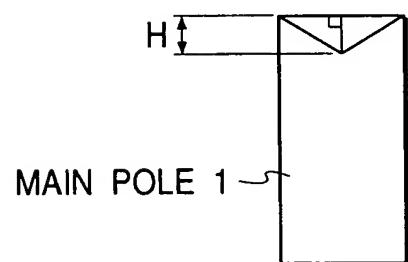


FIG. 8(C)

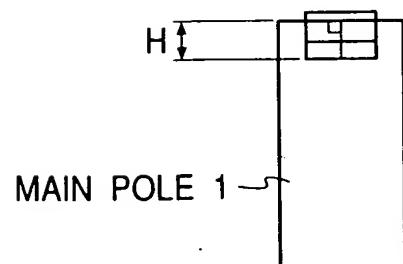
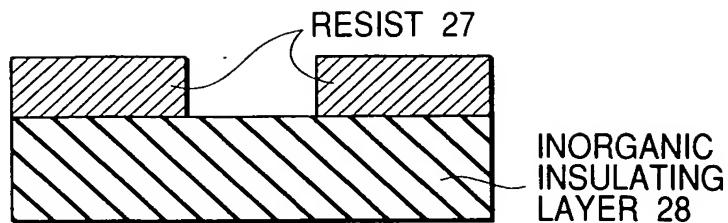
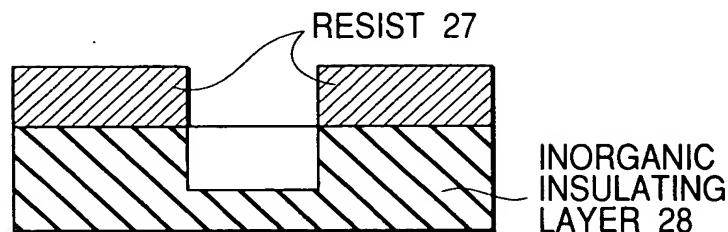


FIG. 9(A)

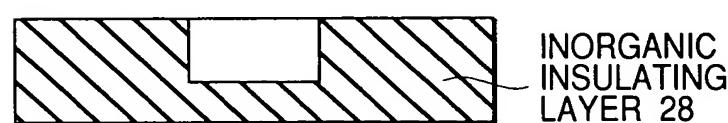
FORMING A
RESIST PATTERN

**FIG. 9(B)**

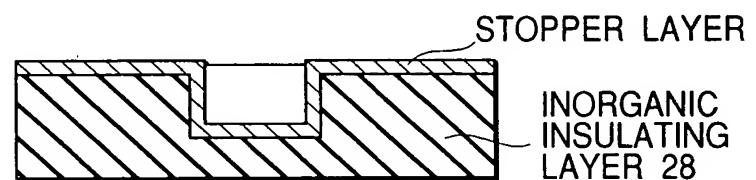
ETCHING THE
INORGANIC INSULATING

**FIG. 9(C)**

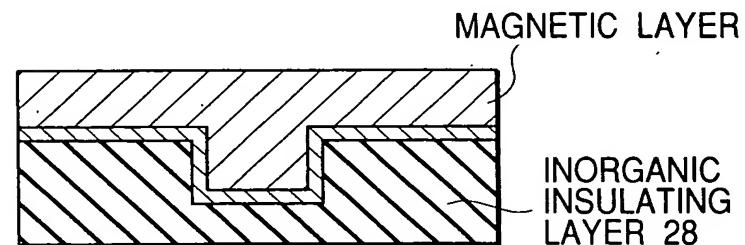
REMOVING THE
RESIST PATTERN

**FIG. 9(D)**

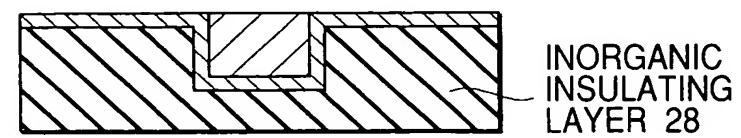
FORMING A
STOPPER LAYER

**FIG. 9(E)**

FORMING A
MAGNETIC LAYER

**FIG. 9(F)**

POLISHING TO FLATTEN
THE MAGNETIC LAYER

**FIG. 9(G)**

FORMING A HOLLOW
OF MAGNETIC LAYER

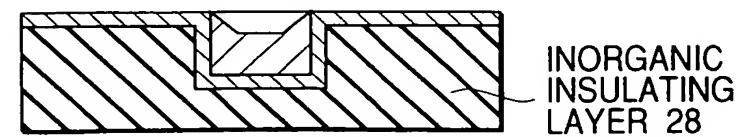
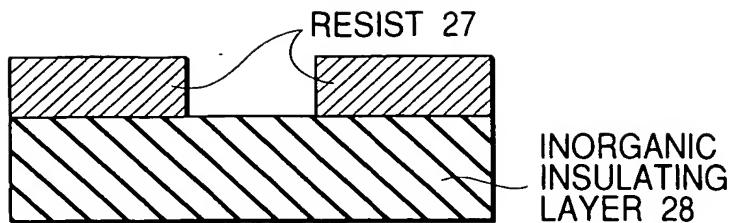
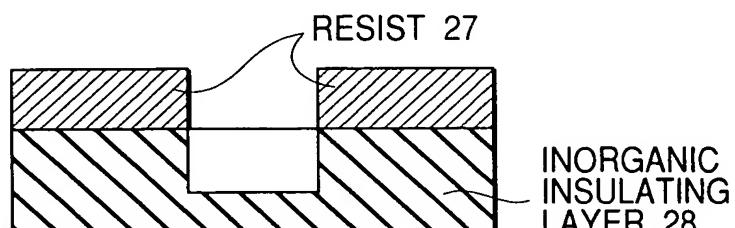


FIG. 10(A)

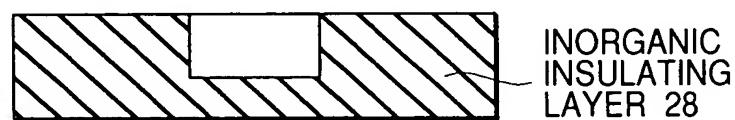
FORMING A
RESIST PATTERN

**FIG. 10(B)**

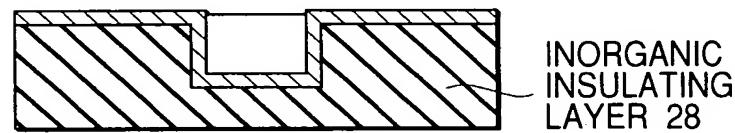
ETCHING AN INORGANIC
INSULATING

**FIG. 10(C)**

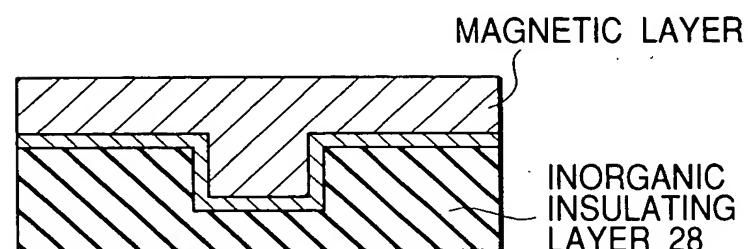
REMOVING THE
RESIST PATTERN

**FIG. 10(D)**

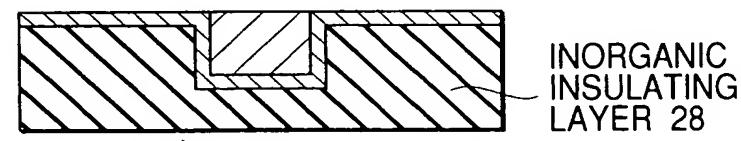
FORMING A
STOPPER LAYER

**FIG. 10(E)**

FORMING A
MAGNETIC LAYER

**FIG. 10(F)**

POLISHING TO FLATTEN
THE MAGNETIC LAYER

**FIG. 10(G)**

FORMING A HOLLOW
OF MAGNETIC LAYER

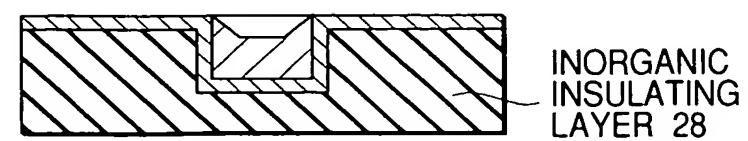


FIG. 11(A)

FORMING A
RESIST PATTERN

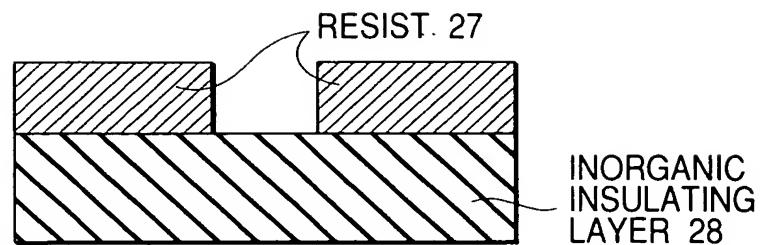


FIG. 11(B)

FORMING A
MAGNETIC LAYER

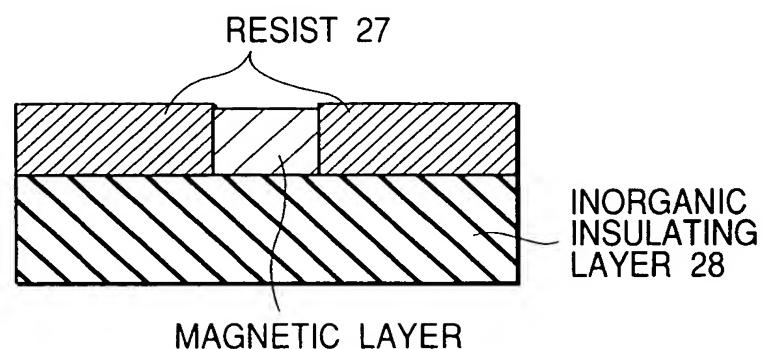


FIG. 11(C)

REMOVING THE
RESIST PATTERN

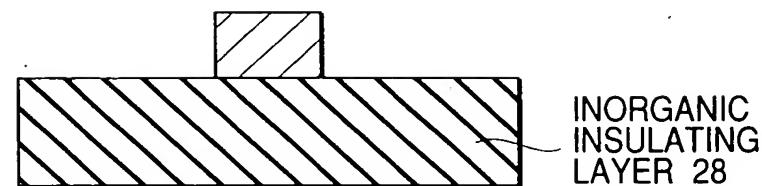


FIG. 11(D)

FORMING A HOLLOW
OF MAGNETIC LAYER

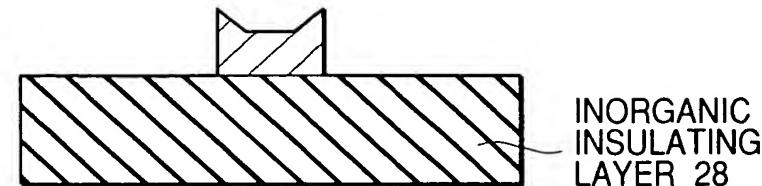
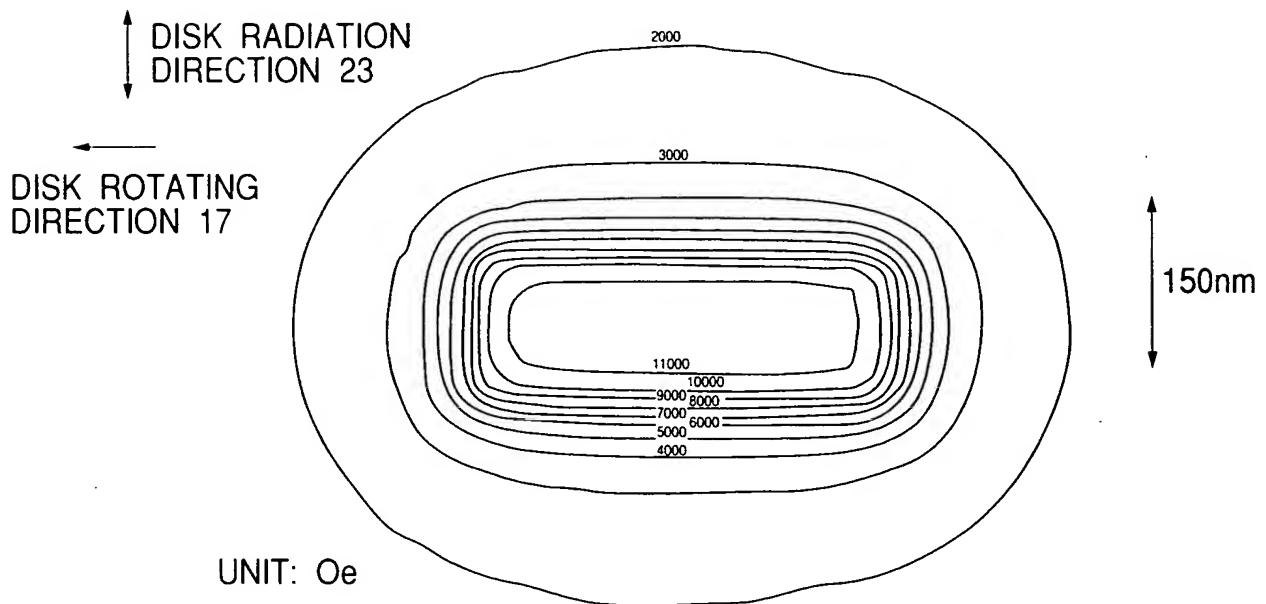


FIG. 12
IN CASE OF A SHALLOW HOLLOW (H=10nm)



CONTOURS OF PERPENDICULAR COMPONENT OF WRITE FIELD GENERATED FROM A SINGLE POLE TYPE HEAD

FIG. 13
IN CASE OF A DEEP HOLLOW (H=200nm)

